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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. 10/071,425
Filing Date February 8, 2002
Inventor Terry L. Gilton et al.
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner Thanhha S. Pham
Attorney Docket No. MI22-1828
Customer No. 021567
Title: Semiconductor Processing Method Using Photoresist and Antireflective
Coating

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

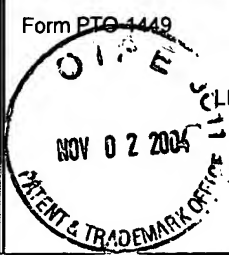
References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. Copies of the cited prior art references are attached. No admission is made regarding whether all the listed references are prior art.

Respectfully submitted,

Dated: 11-1-04

By: 
Mark S. Matkin
Reg. No. 32,268

Form PTO 4449 		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1828		SERIAL NO. 10/071,425	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Terry L. Gilton et al.			
U.S. PATENT DOCUMENTS				FILING DATE February 8, 2002		GROUP 2813	
*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AB						
	AC						
	AD						
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	AG						
	AH						
	AI						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AJ						
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM		Lee et al., <i>Lithographic Properties of SiN_x and Se₇₅Ge₂₅ Thin Films as the Low-Energy Ion-Beam Resist</i> ,				
			5 th International Conference on Properties and Applications of Dielectric Materials, Seoul, Korea				
	AN		(May 25-30, 1997) pp. 635-638.				
	AO						
EXAMINER		DATE CONSIDERED					
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							